L Number	Hits	Search Text	DB	Time stamp
5	102	427/8-10.ccls. not (430/22,30,311,313,322,330.ccls. and (((spin$4 or rotat$3 or centrifug$6) and (expos$3 or radiat$3 or irradiat$3 or light$3) and develop$3) same (resist or photoresist or photosens$5 or photopolymer$7))) and ((etch$3 or heat$3 or bak$3 or prebak$3 or postbak$3) same (resist or photoresist or photosens$5 or photopolymer$7)) not (430/22,30.ccls. not ((((spin$4 or rotat$3 or centrifug$6) and (expos$3 or radiat$3 or irradiat$3 or light$3) and develop$3) same (resist or photoresist or photosens$5 or photopolymer$7))) and ((etch$3 or heat$3 or bak$3 or prebak$3 or postbak$3) same (resist or photoresist or photosens$5 or photopolymer$7)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/14 12:48
6	10	427/8-10.ccls. and (resist or photoresist) same (nozzle or dispens$3 or spread$3 or pip$3 or eject$3) near3 (accelerat$3 or decelerat$3 or position$3 or location)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/14 15:01
7	10	427/8-10.ccls. and (resist or photoresist) same (nozzle or dispens$3 or spread$3 or pip$3 or eject$3) same (accelerat$3 or decelerat$3 or position$3 or location) not (427/8-10.ccls. and (resist or photoresist) same (nozzle or dispens$3 or spread$3 or pip$3 or eject$3) near3 (accelerat$3 or decelerat$3 or position$3 or location))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/14 15:04
-	1	("20020037462").PN.	USPAT; US-PGPUB	2003/01/21 11:31
-	2	(("6051349") or ("5968691")).PN.	USPAT; US-PGPUB	2003/03/31 15:25
-	28	(("6541170") or ("6457882") or ("6431769") or ("6281962") or ("6266125") or ("6221787") or ("5845170") or ("5939130") or ("6543080") or ("6492271") or ("5879854") or ("6185472") or ("6001461") or ("5817174") or ("6436723") or ("6431185") or ("6010797") or ("6118280") or ("5485549") or ("6398429") or ("5908657") or ("6444029") or ("6033475") or ("6023084") or ("5831300") or ("5933726") or ("5933724") or ("5804479") or ("5937290")).PN.	USPAT; US-PGPUB	2003/04/01 17:47
-	13	((("6541170") or ("6457882") or ("6431769") or ("6281962") or ("6266125") or ("6221787") or ("5845170") or ("5939130") or ("6543080") or ("6492271") or ("5879854") or ("6185472") or ("6001461") or ("5817174") or ("6436723") or ("6431185") or ("6010797") or ("6118280") or ("5485549") or ("6398429") or ("5908657") or ("6444029") or ("6033475") or ("6023084") or ("5831300") or ("5933726") or ("5933724") or ("5804479") or ("5937290")).PN.) and (((spin$4 or rotat$3 or centrifug$3) and (expos$3 or radiat$3 or irradiat$3 or light$3) and develop$3) same (resist or photoresist or photosens$5 or photopolymer$7)	USPAT; US-PGPUB	2003/04/01 18:32
-	1695	430/22,30,311,313,322,330.ccls. and (((spin$4 or rotat$3 or centrifug$6) and (expos$3 or radiat$3 or irradiat$3 or light$3) and develop$3) same (resist or photoresist or photosens$5 or photopolymer$7))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/01 18:34

-	1589	(430/22,30,311,313,322,330.ccls. and (((spin$4 or rotat$3 or centrifug$6) and (expos$3 or radiat$3 or irradiat$3 or light$3) and develop$3) same (resist or photoresist or photosens$5 or photopolymer$7))) and ((etch$3 or heat$3 or bak$3 or prebak$3 or postbak$3) same (resist or photoresist or photosens$5 or photopolymer$7))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/10 19:46
-	603	(430/22,30.ccls. not ((((spin$4 or rotat$3 or centrifug$6) and (expos$3 or radiat$3 or irradiat$3 or light$3) and develop$3) same (resist or photoresist or photosens$5 or photopolymer$7))) and ((etch$3 or heat$3 or bak$3 or prebak$3 or postbak$3) same (resist or photoresist or photosens$5 or photopolymer$7)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/10 19:33
-	1283	430/30.ccls. not (430/22,30.ccls. not ((((spin$4 or rotat$3 or centrifug$6) and (expos$3 or radiat$3 or irradiat$3 or light$3) and develop$3) same (resist or photoresist or photosens$5 or photopolymer$7))) and ((etch$3 or heat$3 or bak$3 or prebak$3 or postbak$3) same (resist or photoresist or photosens$5 or photopolymer$7)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/10 19:38
-	40	(430/30.ccls. not (430/22,30.ccls. not ((((spin$4 or rotat$3 or centrifug$6) and (expos$3 or radiat$3 or irradiat$3 or light$3) and develop$3) same (resist or photoresist or photosens$5 or photopolymer$7))) and ((etch$3 or heat$3 or bak$3 or prebak$3 or postbak$3) same (resist or photoresist or photosens$5 or photopolymer$7)))) and ((accelerat$4 or speed$3 or rotat$4 or spin$4) same (resist or photoresist or photosens$5 or photopolymer$7) same (nozzle or pipe or spread$3 or dispens$3 or flow$3))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/10 19:43
-	0	(430/30.ccls. not (430/22,30.ccls. not ((((spin$4 or rotat$3 or centrifug$6) and (expos$3 or radiat$3 or irradiat$3 or light$3) and develop$3) same (resist or photoresist or photosens$5 or photopolymer$7))) and ((etch$3 or heat$3 or bak$3 or prebak$3 or postbak$3) same (resist or photoresist or photosens$5 or photopolymer$7)))) and ((accelerat$4 or speed$3 or rotat$4 or spin$4) same (resist or photoresist or photosens$5 or photopolymer$7) same (nozzle or pipe or spread$3 or dispens$3 or flow$3)) not (430/22,30,311,313,322,330.ccls. and (((spin$4 or rotat$3 or centrifug$6) and (expos$3 or radiat$3 or irradiat$3 or light$3) and develop$3) same (resist or photoresist or photosens$5 or photopolymer$7))) and ((etch$3 or heat$3 or bak$3 or prebak$3 or postbak$3) same (resist or photoresist or photosens$5 or photopolymer$7))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/12 12:54

-	5	427/8-10 not (430/22,30,311,313,322,330.ccls. and (((spin$4 or rotat$3 or centrifug$6) and (expos$3 or radiat$3 or irradiat$3 or light$3) and develop$3) same (resist or photoresist or photosens$5 or photopolymer$7))) and ((etch$3 or heat$3 or bak$3 or prebak$3 or postbak$3) same (resist or photoresist or photosens$5 or photopolymer$7)) not (430/22,30.ccls. not ((((spin$4 or rotat$3 or centrifug$6) and (expos$3 or radiat$3 or irradiat$3 or light$3) and develop$3) same (resist or photoresist or photosens$5 or photopolymer$7))) and ((etch$3 or heat$3 or bak$3 or prebak$3 or postbak$3) same (resist or photoresist or photosens$5 or photopolymer$7)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/14 12:42
-	66	(substrate or wafer) near3 (defect or fault) same (nozzle or pipe or spread$3 or flow$3 or dispens$3) same (resist or photoresist or photosens$5 or photopolymer$7)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/10 20:02
-	1	"5489337".PN.	USPAT; US-PGPUB	2003/04/11 09:53
-	1	"5912054".PN.	USPAT; US-PGPUB	2003/04/11 10:22
-	1	("5409538").PN.	USPAT; US-PGPUB	2003/04/11 16:07